

Su	ASSIFI
Class	SSUE CLA

U.S. **UTILITY** Patent Application

mT	O.I.P.E.	0
"7	1-0	LAK.
SCANNED	KMIL	150

PATENT DATE

1	1-010	
SCANNED	C(1/o.A.V)	_

	<del> </del>	<del></del>	and the second s			•
	PLICATION NO. 09/992054	CONT/PRIOR	CLASS 525 20	SUBCLASS	ART UNIT	EXAMINER COSCORT
APPLICANTS	Aref Jallo Joey Oboro Yassin Tu Peigi Jia	do rshani		·		
	High index	x and hig	h impaçt	resistan	t polythiou	urethane/urea

material, method of manufacturing same and its use in the optical field

ISSUING CLASSIFICATION					
ORIGIN	AL	CROSS REFERENCE(S)			
CLASS SUBCLASS	CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)			
INTERNATIONA	L CLASSIFICATION				
		- · · · ·			
			☐ Continued on Issue Slip Inside File Jacket		

TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
☐ The term of this patent				NOTICE OF ALLOWANCE MAILED	
subsequent to (date) has been disclaimed.	(Assistant I	Examiner)	(Date)	4: #	
The term of this patent shall					
not extend beyond the expiration date of U.S Patent. No.				ISS	UE FEE
. <del></del>				Amount Due	Date Paid
<u></u>	(Primary E	xaminer)	(Date)		•
☐ The terminalmonths of				ISSUE BATCH NUMBER	
this patent have been disclaimed.	(Legal Instrume	nts Examiner)	(Date)		
WARNING: The information disclosed herein may be rest Possession outside the U.S. Patent & Tradem	ricted. Unauthorized of ark Office is restricted	fisclosure may be to authorized empl	prohibited by the U	nited States Code Title 39	5, Sections 122, 181 and 368
orm PTO-436A (ev. 6/99)			FILED WITH:	DISK (CRF)	FICHE CD-RO

(FACE)